ABSTRACT OF THE DISCLOSURE

From the region near the target pattern, patterns whose barycenter positions are not changed even if deformation is generated due to proximity effect or coarse-and-fine difference at the time of pattern forming are selected as alignment patterns, and the barycenter positions thereof are set as alignment reference coordinates. Rough alignment is carried out based on the reference position provided in a region other than the device forming region, thereby detecting the alignment pattern in the device forming region. Positioning is carried out such that the alignment reference coordinates of the alignment patterns and the center coordinates of the target pattern coincide with each other, and the target pattern is detected.